

U.S. Department of Commerce, Patent and Trademark Office

Docket No.:

4260/P1/CMP/CMP/RKK

Serial No.:

09/843,582

LIST OF RELEVANT ART CITED BY APPLICANT

(Use several sheets if necessary)

Applicants:

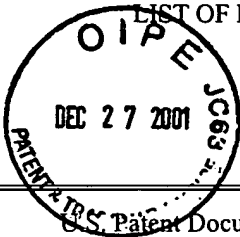
Yuchun Wang, Rajeev Bajaj and Fred C. Redeker

Filing Date:

4/26/01

Group: 3723

unknown



U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
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	AE						
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	AI						
	AJ						
	AK						

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DEC 31 2001

TECHNOLOGY CENTER R3700

Foreign Patent Documents

Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
DVN	AL	00/44034✓	07/27/00	World				
	AM							
	AN							
	AO							
	AP							

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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Examiner

Date Considered

Jimmy van Nguyen

2-20-2002

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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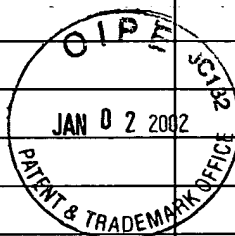
April 26, 2001

Group:

3723
1744

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
DVN	AA	6,022,264✓	02/08/00	Cook et al.			
DVN	AB	6,022,268✓	02/08/00	Roberts et al.			
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	AJ						
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	AL							
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*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
DVN	AA	4,169,337✓	10/02/79	Payne			
	AB	4,588,421✓	05/13/86	Payne			
	AC	4,752,628✓	06/21/88	Payne			
	AD	4,867,757✓	09/19/89	Payne			
	AE	5,264,010✓	11/23/93	Brancaleoni et al.			
	AF	5,614,444✓	03/25/97	Farkas et al.			
	AG	5,700,383✓	12/23/97	Feller et al.			
	AH	5,738,574✓	04/14/98	Tolles et al.			
	AI	5,738,800✓	04/14/98	Hosali et al.			
	AJ	5,756,398✓	05/26/98	Wang et al.			
	AK	5,769,689✓	06/23/98	Cossaboon et al.			

Foreign Patent Documents

Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
DVN	AL	98/49723✓	11/05/98	World				
	AM	0 913 442 A2✓	05/06/99	Europe				
	AN	00/30159✓	05/25/00	World				
	AO	00/36037✓	06/22/00	World				
	AP	00/49647✓	08/24/00	World				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

DVN	AR✓	V. Brusic, et al., "Copper Corrosion With and Without Inhibitors", Electrochemical Society, Inc. 138:8, pp.2253-2259 (August 1991).
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<i>dvw</i> ↓	AA	5,840,629✓	11/24/98	Carpio			
	AB	5,876,508✓	03/02/99	Wu et al.			
	AC	5,911,835✓	06/15/99	Lee et al.			
	AD	5,932,486✓	08/03/99	Cook et al.			
	AE	5,958,794✓	09/28/99	Bruxvoort et al.			
	AF	5,981,454✓	11/09/99	Small			
	AG	6,033,993✓	03/07/00	Love, Jr. et al.			
	AH	6,042,741✓	03/28/00	Hosali et al.			
	AI	6,046,110✓	04/04/00	Hirabayashi et al.			
	AJ	6,054,379✓	04/25/00	Yau et al.			
	AK	6,068,879✓	05/30/00	Pasch			

Foreign Patent Documents							Translation	
Document Number	Date	Country	Class	Subclass	Yes	No		
<i>dvw</i>	AL	00/53691✓	09/14/00	World				
	AM							
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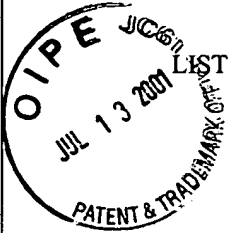
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DVN	AA	6,077,337 ✓	06/20/00	Lee			
	AB	6,083,840 ✓	07/04/00	Mravic et al.			
	AC	6,096,652 ✓	08/01/00	Watts et al.			
	AD	6,099,604 ✓	08/08/00	Sandhu et al.			
	AE	6,117,775 ✓	09/12/00	Kondo et al.			
	AF	6,117,783 ✓	09/12/00	Small et al.			
	AG	6,123,088 ✓	09/26/00	Ho			
	AH	6,136,218 ✓	10/24/00	Skrovan et al.			
	AI	6,136,714 ✓	10/24/00	Schutz			
	AJ	6,156,661 ✓	12/05/00	Small			
✓	AK	09/401,643 ✓		Li et al.			09/22/99

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dvN	AA	09/469,708 ✓	Li et al.			12/21/99	
	AB	09/543,777 ✓	Sun et al.			4/05/00	
	AC	09/544,281 ✓	Sun et al.			4/06/00	
	AD	09/569,968 ✓	Sun et al.			5/11/00	
	AE	09/606,544 ✓	Sun et al.			6/30/00	
	AF	09/608,078 ✓	Sun et al.			6/30/00	
	AG	09/694,866 ✓	Wang et al.			10/23/00	
	AH	09/698,863 ✓	Tsai et al.			10/27/00	
	AI	09/698,864 ✓	Sun et al.			10/27/00	
	AJ	09/741,538 ✓	Li et al.			12/20/00	
✓	AK	09/247,381 ✓	Cheung et al.			2/02/01	

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